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PTO/SB/08B (08-09)

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Substitute for form 1449B/PTO

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INFORMATION DISCLOSURE
STATEMENT BY APPLICANT

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Sheet

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of

3

Application Number	10/085,759
Filing Date	28 February 2002
First Named Inventor	Michel L. Cote
Group Art Unit	1756
Examiner Name	Stephen D. Rosasco

Attorney Docket Number

NMTI 1002-6

OTHER PRIOR ART – NON PATENT LITERATURE DOCUMENTS

Examiner Initials*	Cite No.†	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	TP
	C1	SAKATA, MIWA, et al., "A Novel Radiation Sensitive Spin-on-glass Convertible into SiO ₂ and the Simple Fabrication Process Using It," 26 July 1993* (*AT&T Bell Labs fax date), 3 pages.	
	C2	PISTOR, THOMAS V., "Rigorous 3D Simulation of Phase Defects in Alternating Phase-Shifting Masks," Proceedings of SPIE 4562-1038 (March 2002), 13 pages	
		OGAWA, KIYOSHI, et al., "Phase Defect Inspection by Differential Interference," Proceedings of SPIE 4409-71, 26 April 2001, 12 pages.	
		RHYINS, P., et al., "Characterization of Quartz Etched PSM Masks for KrF Lithography at the 100 nm node," Proceedings of SPIE 4562 (March 2002), 486-495.	
		SEWELL, HARRY, et al., "An Evaluation of the Dual Exposure Technique," (As early as 2002*), 11 pages *The date is based on references 8&9 of the article of 16 Feb 2001 and 27 Feb 2002, respectively.	
		WANG, RUOPING, et al., "Polarized Phase Shift Mask: Concept, Design, and Potential Advantages to Photolithography Process and Physical Design," Proceedings of SPIE 4754-105, 25 April 2002, 12 pages.	
		MATSUOKA, et al., "Application of Alternating Phase-Shifting Mask to 0.16um CMOS Logic Gate Patterns," SPIE Proc. 3051, March 10-14, 1997, 10 pages.	
		SEMMIER, ARMIN, et al., "Application of 3D EMF Simulation for Development and Optimization of Alternating Phase Shifting Masks," Proc. of SPIE 4346-37, 1 March 2001, 12 pages.	
		WONG, ALFRED K., "Polarization Effects in Mask Transmission," Proc. of SPIE 1674, 8 March 1992, 8 pages.	
		ACKMANN, PAUL, et al., "Phase Shifting and Optical Proximity Corrections to improve CD control on Logic Devices in Manufacturing for sub 0.35 um 1-Line," Proc. of SPIE 3051-07, March 1997, 8 pages.	
		SPENCE, C., et al., "Detection of 60 degree Phase defects on Alternating PSMs," Proc. of SPIE 3412-73, April 1998, 2 pages	

Examiner Signature



Date Considered

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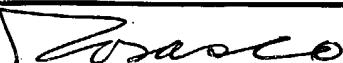
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				Attorney Docket Number	NMTI 1002-6

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		SUGAWARA, MINORU, et al., "Defect printability study of attenuated phase-shifting masks for specifying inspection sensitivity," Proc. SPIE 2621-49, September 1995, 16 pages	
		SCHMIDT, REGINA, et al., "Impact of Coma on CD Control for Multiphase PSM Designs," Proc. SPIE 3334-02, February 1998, 11 pages	
		ERDMANN, ANDREAS, "Topography effects and wave aberrations in advanced PSM-technology," Proc. SPIE 4346-36, 1 March 2001, 28 pages	
		GRANIK, YURI et al., "CD variation analysis technique and its application to the study of PSM mask misalignment," Proc. SPIE 4186-94, September 2000, 9 pages	
		ISHIWATA, NAOYUKI, et al., "Fabrication of Phase-Shifting Mask," Proc. SPIE 1463, March 1991, 11 pages	
		LEVENSON, MARC D., et al., "Phase First! An improved strong-PSM paradigm," Proc. SPIE 4186-42, September 2000, 10 pages	
		LEVENSON, MARC. D., et al., "SCAA mask exposures and Phase First design for 110nm and below," Proc. SPIE 4346-817, September 2001, 10 pages	
		MORIKAWA, YASUTAKA, et al., "100nm-Alt.PSM structure discussion for ArF lithography," Proc. SPIE 4409-22, April 2001, 15 pages	
		OZAKI, T., et al., "A 0.15um KrF Lithography for 1Gb DRAM Product using Highly Printable Patterns and Thin Resist Process," 1998 Symposium on VLSI Technology, June 1998, Honolulu, Hawaii, 2 pages	
		RONSE, KURT, et al., "Comparison of various phase shift strategies and application to 0.35 um ASIC designs," Proc. SPIE 1927, 1993, 15 pages	
		ROSENBLUTH, ALAN E., et al., "Optimum Mask and Source Patterns to Print a Given Shape," Proc. SPIE 4346-49, 1 March 2001, 17 pages	
			

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